In re Appln. of KAWASAKI et al. Application No. Unassigned

CLAIM AMENDMENTS

1. (Currently Amended) A method for of manufacturing a semiconductor optical device comprising:

step-for-forming growing an epitaxial growth layer structure containing at least an active layer which can emit light, using of a III-V group semiconductor material including a group V element;

step for forming an insulation insulating layer over the epitaxial growth layer structure, which can prevent the V group element from escaping during heat treatment;

step for applying heat treatment to treating the epitaxial-growth layer structure at a temperature of at least 800 degree- degrees C-or more;

step for removing the insulation insulating layer.

- 2. (Currently Amended) The method for of manufacturing a semiconductor optical device according to Claim 1 comprising step for performing PL a photoluminescence measurement after the heat-treatment step treating.
- 3. (Currently Amended) A semiconductor optical device comprising an epitaxial growth layer formed structure of a III-V group semiconductor material, containing at least an active layer which can emit light, wherein the composition of the epitaxial growth layer is changing structure continuously changes near the an interface.
- 4. (Currently Amended) The semiconductor optical device according to Claim 3, wherein a photoluminescence wavelength of the optical device is blue-shifted, as compared to a semiconductor optical device which has an active layer with the same composition as said active layer and an epitaxial growth layer whose structure with a composition is changed that changes stepwise near the interface.
- 5. (Currently Amended) The semiconductor optical device according to Claim 4, wherein the photoluminescence wavelength is blue-shifted by <u>at least</u> 20 meV or more.
- 6. (Currently Amended) The semiconductor optical device according to Claim 3, wherein distortion between of the epitaxial growth layers structure is more eased, as reduced compared to a semiconductor optical device which has an active layer with the same

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composition as said active layer and an epitaxial growth-layer whose structure with a composition is changed changing stepwise near the interface.